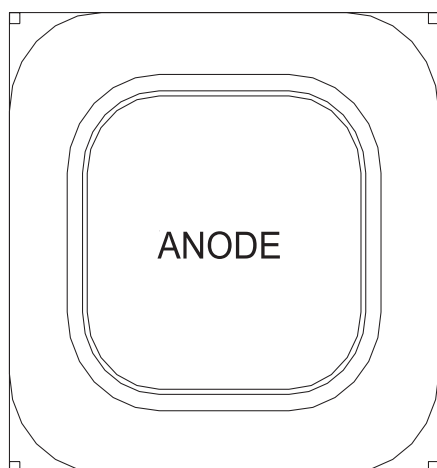


PROCESS DETAILS

Process	EPITAXIAL PLANAR
Die Size	14 x 14 MILS
Die Thickness	7.1 MILS
Anode Bonding Pad Area	9.0 x 9.0 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 12,000Å

GEOMETRY



R1

BACKSIDE CATHODE

GROSS DIE PER 4 INCH WAFER

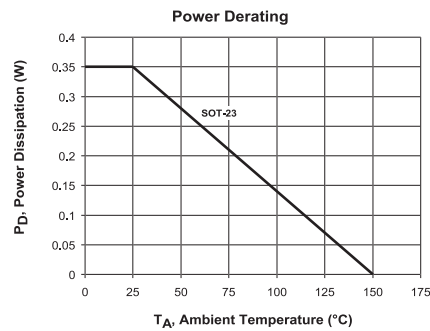
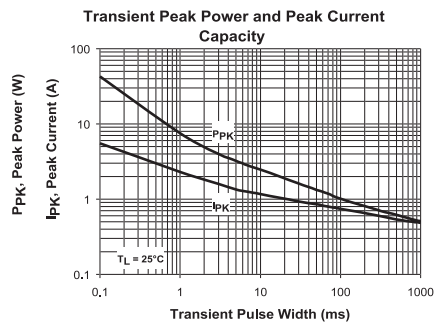
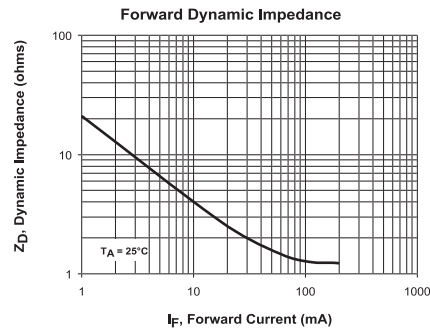
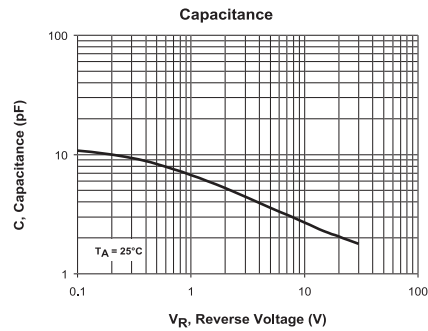
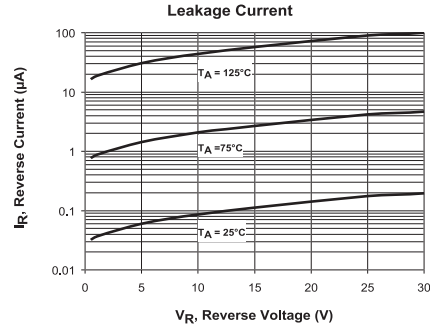
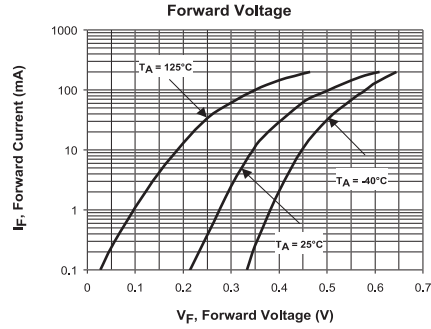
62,250

PRINCIPAL DEVICE TYPES

CMPSH-3 Series
CMSSH-3 Series
CMXSH-3
CMKSH-3T

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